## INVENTOR INFORMATION

Inventor One Given Name::

Family Name::

Mailing Address Line One::

Mailing Address Line Two::

City::

Country::

City of Residence:: Country of Residence::

Citizenship Country::

Inventor Two Given Name::

Family Name::

Mailing Address Line One::

Mailing Address Line Two::

City::

Country::

City of Residence::

Country of Residence::

Citizenship Country::

Inventor Three Given Name::

Family Name::

Mailing Address Line One::

Mailing Address Line Two::

City::

Country::

City of Residence::

Country of Residence::

Citizenship Country::

CORRESPONDENCE INFORMATION

CORRESPONDENCE INFORMATION

Correspondence Customer Number::

APPLICATION INFORMATION

Title Line One::

Title Line Two::

Application Type::

Docket Number::

REPRESENTATIVE INFORMATION

Representative Customer Number::

PRIOR FOREIGN APPLICATIONS

Foreign Application One::

Filing Date::

Country::

Priority Claimed::

ASSIGNEE INFORMATION

Jun

HATAKEYAMA

c/o Shin-Etsu Chemical Co., Ltd.

28-1, Oaza Nishifukushima, Kubiki-mura

Nakakubiki-gun, Niigata-ken

Japan

Nakakubiki-gun, Niigata-ken

Japan

Japan

Jun

WATANABE

c/o Shin-Etsu Chemical Co., Ltd.

28-1, Oaza Nishifukushima, Kubiki-mura

Nakakubiki-gun, Niigata-ken

Japan

Nakakubiki-gun, Niigata-ken

Japan

Japan

Yuji HARADA

1M(ADA

c/o Shin-Etsu Chemical Co., Ltd.

28-1, Oaza Nishifukushima, Kubiki-mura

Nakakubiki-gun, Niigata-ken

Japan

Nakakubiki-gun, Niigata-ken

Japan

Japan

23599

POLYMER, CHEMICALLY AMPLIFIED RESIST

COMPOSITION AND PATTERNING PROCESS

UTILITY

KOJIM-393

23599

2000-127513

4/27/2000

Japan

YES

Name of Assignee::
Address Line One::
City::
State or Province::
Country::

Shin-Etsu Chemical Co., Ltd. 6-1, Otemachi, 2-chome Chiyoda-ku, Tokyo Tokyo Japan